JUL 3 0 2004

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):

Chiang, Tony P.; Leeser, Karl F.

Assignee:

Novellus Systems, Inc. (reassigned)

Title:

Method for Integrated In-Situ Cleaning and Subsequent Atomic Layer

Deposition Within a Single Processing Chamber

Serial No.:

09/994,279

Filing Date:

November 26, 2001

Examiner:

David Nhu

Group Art Unit:

2818

Docket No.:

PA1688 US

San Jose, California
July 30, 2004

Mail Stop Petition
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO FINAL OFFICE ACTION

Dear Sir:

This responds to the Office Action dated February 5, 2003, in the above-identified application. The application was unintentionally abandoned, and the appropriate petition for revival is enclosed herewith. Please amend the application to place all claims in condition for allowance as follows.

Amendments to the claims begin on page 2.

Amendments to the specification begin on page 7.

Remarks begin on page 8.

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